

# Oleg B Khristoforov

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/1384915/publications.pdf>

Version: 2024-02-01

15  
papers

130  
citations

1937685

4  
h-index

1588992

8  
g-index

15  
all docs

15  
docs citations

15  
times ranked

82  
citing authors

#	ARTICLE	IF	CITATIONS
1	High-power, highly stable KrF laser with a 4-kHz pulse repetition rate. Quantum Electronics, 2015, 45, 691-696.	1.0	4
2	EUV light source with high brightness at 13.5 nm. Quantum Electronics, 2014, 44, 1077-1082.	1.0	4
3	A toxicity estimation system for individual hydrocarbons in the monitoring loop of emergency oil spills on water bodies. Automation and Remote Control, 2014, 75, 2023-2033.	0.8	0
4	Creation and investigation of powerful EUV sources ( $\lambda = 13.5$ nm). Plasma Physics Reports, 2010, 36, 216-225.	0.9	2
5	Laser-induced extreme UV radiation sources for manufacturing next-generation integrated circuits. Quantum Electronics, 2009, 39, 967-972.	1.0	3
6	EUV sources using Xe and Sn discharge plasmas. Journal Physics D: Applied Physics, 2004, 37, 3254-3265.	2.8	59
7	<title>Recent advances in the development of coherent and incoherent UV and EUV discharge sources</title>. , 2004, , .		0
8	High-power EUV sources for lithography: a comparison of laser-produced plasma and gas-discharge-produced plasma. , 2002, , .		13
9	Development of high-power EUV sources for lithography. , 2002, 4688, 626.		14
10	High-power gas-discharge EUV source. Plasma Physics Reports, 2002, 28, 877-881.	0.9	4
11	Prospects for high-power high-repetition-rate industrial excimer lasers. , 2001, 4184, 348.		2
12	<title>Compact Z-pinch EUV source for photolithography</title>. , 2001, , .		10
13	Efficient preionisation in XeCl lasers. Quantum Electronics, 1999, 29, 204-208.	1.0	6
14	Powerful highly efficient KrF lamps excited by surface and barrier discharges. Quantum Electronics, 1998, 28, 297-303.	1.0	6
15	High-average-power excimer lasers. , 1998, 3574, 56.		3